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Photonic and Plasmonic Guided Modes in Graphene–Silicon Photonic Crystals

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Supporting Information

ABSTRACT: We report the results of systematic studies of plasmonic and photonic guided modes in large-area single-layer graphene integrated into a nanostructured silicon substrate. The interaction of light with graphene and substrate photonic crystals can be classified in distinct regimes depending on the relation of the photonic crystal lattice constant and the relevant modal wavelengths, that is, plasmonic, photonic, and free-space. By optimizing the design of the substrate, these resonant modes can increase the absorption of graphene in the infrared, facilitating enhanced



performance of modulators, filters, sensors, and photodetectors utilizing silicon photonic platforms.

KEYWORDS: graphene absorption, graphene plasmonic response, silicon photonics, infrared response, absorption enhancement

he continuous miniaturization of components in silicon photonics provides a platform to enable applications in densely integrated communication and computing systems.¹ The high refractive index and low absorption of silicon allow for low-loss waveguiding from the terahertz to the telecommunication spectral range in the near-infrared, but its band gap of 1.1 eV renders silicon an inefficient material for photodetection in this long wavelength range. Hence, photonic systems based on alternative materials, such as III-V semiconductors² and graphene,³ are sought for those applications.⁴ In particular, graphene is a promising material since it supports mid-infrared plasmons^{5,6} with light confinement down to 1/100 of the free-space wavelength λ_0 , as well as tunability of electrical conductivity, thus, allowing the creation of active devices⁷ not possible with conventional metal plasmonics. Graphene plasmons have already been experimen-tally observed⁷⁻¹² and explored for terahertz and infrared absorption, modulation, photodetection, and chemical sensing.13-18 Furthermore, graphene can be easily integrated with silicon photonics components for more efficient light management schemes.^{14,19}

One of the challenges for the excitation and use of surface plasmon polaritons in graphene is the phase (wavevector) mismatch between these guided waves and the incident electromagnetic radiation. Graphene nanostructures, such as one-dimensional (1D) nanoribbon arrays^{11,12,20} and two-dimensional (2D) rectangular resonator arrays,²¹ dot⁷ and

antidot lattices,^{22,23} and plasmonic crystals,²⁴ provide a natural approach to coupling free-space radiation to graphene plasmons. However, these schemes require that the graphene layer be patterned, which introduces additional loss channels from atomic scale roughness of the edges.^{11,25} It is therefore attractive to couple to graphene plasmons by the alternate approach of patterning the substrate, leaving the graphene layer in its pristine state and preserving its excellent electronic properties.

The case of a 1D grating etched into a silicon substrate with a graphene overlayer has been studied theoretically for mid-IR plasmon excitation²⁶ and subsequently investigated experimentally in a hexagonal 2D grating configuration.²⁷ These configurations exploit the difference in the effective mode index between plasmons in a silicon–graphene–air structure (graphene on silicon) and in a suspended air–graphene–air structure (graphene over holes), in addition to using the associated contrast of the dynamic conductivity.²⁸ At the same time, photonic modes within the silicon grating can also be excited. These photonic modes can be used to increase the absorbance in graphene, as was recently demonstrated.^{29–33} In this work, we explore the various regimes of light–matter interaction in the infrared spectral range for graphene integrated with a silicon photonic crystal membrane. We

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Figure 1. Suspended graphene superlattice. (a) SEM image combined with a sketch of the plasmonic and photonic modes excited by a normally incident plane wave. (b) SEM top view of the graphene–photonic crystal structure. (c) Histogram of the topology measured by AFM. The experimental peak is decomposed into a part corresponding to suspended graphene (over holes, fwhm of 1.72 nm) and to supported graphene (on silicon, fwhm of 5.31 nm), with a 0.57 nm height difference. (d) AFM image of the surface stiffness of graphene on a silicon photonic crystal membrane for different disk radii: r = (i) 90, (ii) 100, (iii) 110, (iv) 120, (v) 130, and (vi) 140 nm and the corresponding 2D spatial Fourier transforms (i'–vi', respectively). The lattice constant is a = 415 nm and the scale bars is 1 μ m in length.

demonstrate experimentally the possibility of light coupling to the graphene plasmonic modes and to the photonic guided modes of the underlying substrate. We examine theoretically the physical mechanisms and factors controlling the crossover between these regimes.

STRUCTURES INVESTIGATED AND THEIR CLASSIFICATION

A scanning electron micrograph of a representative structure consisting of graphene on a photonic crystal membrane is presented in Figure 1a. The different regimes of light coupling to the structure can be categorized based on the feature size of the structure (particularly the lattice constant *a*), the effective wavelengths for the plasmonic (λ_{pl}) and photonic crystal (λ_{pc}) modes, and the incident (vacuum) wavelength of the light (λ_0). We consider the typical regime for which $\lambda_{pl} < \lambda_{pc} < \lambda_0$ and assume incident light from the vacuum. We identify four regimes of interest:

1. $a < \lambda_{pl}$: Metamaterial Regime. In order to excite a guided wave efficiently at normal incidence, the distance between scatterers in a periodic array should be equal to an integral multiple of the effective wavelength of the guided mode. This condition clearly cannot be met in the of $a < \lambda_{pl}$ and we can consequently consider graphene as a plasmonic metamaterial (or metasurface), since no guided surface waves can be excited due to the pronounced phase mismatch. The incident wave can only be reflected, transmitted, and absorbed in the graphene layer. (Absorption in silicon substrate is low for the relevant spectral range.) The structured silicon substrate can be considered as a homogeneous layer with an anisotropic dielectric response.³⁴

2. $\lambda_{pl} < a < \lambda_{pc}$: **Plasmonic Regime.** In this regime, in addition to transmission and reflection of the incident radiation,

coupling of the incident light to plasmonic modes becomes possible at certain frequencies. This coupling occurs when phase matching is achieved, i.e., for incident waves with propagation constant $\beta = qk_0 = (2\pi/a)m$, where q is the effective mode index, $k_0 = 2\pi/\lambda_0$ is the free-space wavevector of the light, and m is an integer. The incident wave couples to graphene plasmons that are tightly confined by the graphene layer. Their energy is partially absorbed by the graphene and partially coupled back to free space.

3. $\lambda_{pc} < a < \lambda_0$: **Photonic Regime.** In addition to the aforementioned channels, in this regime, the incident wave can couple to the photonic modes of the membrane. Radiation is then absorbed by graphene, which acts mostly as a lossy medium. The photonic modes depend not only on the grating lattice constant, but also on the thickness of the silicon layer. Since we assume light coupling from a normally incident plane wave, we are concerned with the photonic modes that are normally considered as leaky.

4. $\lambda_0 < a$: **Diffraction Grating Regime.** In this regime, the periodic structure becomes a diffraction grating and the incident power is distributed among various diffraction orders, in addition to excitation of the photonic and plasmonic modes described above.

We note that for sufficiently large lattice constant a, all these types of coupling are possible simultaneously, though they are usually important in different frequency ranges. The metamaterial regime for absorbers is well-known,³⁵ while the diffraction grating regime is not particularly suitable for absorbers, since the incident power is predominantly scattered back into free space. In this work, we consequently explore both experimentally and theoretically the most interesting plasmonic and photonic regimes (see illustration in Figure 1a).

Hexagonal 2D silicon photonic crystal membranes were fabricated on a 250 nm thick silicon-on-insulator layer by deep ultraviolet photolithography (248 nm) and etched to reduce disorder scattering.³⁶ The silicon layer is intrinsic, with an estimated doping level of 10^{15} cm⁻³. The lattice constant of the photonic crystal was chosen as 415 nm, with hole radii varying from 80 to 140 nm in 10 nm steps, corresponding, respectively, to silicon filling fractions of 0.87–0.59. The sacrificial release of the supporting silicon oxide buffer layer was performed by wet etching, resulting in a 0.5 μ m air gap between photonic crystal membrane and the underlying silica substrate (Figure S1).

Large-area graphene monolayers were grown on copper film by a chemical vapor deposition (CVD) process.³ The thickness and crystallinity of the graphene layers were characterized by means of Raman spectroscopy (data not shown). The graphene layers were then transferred onto patterned photonic crystal substrates by a PMMA-assisted method (Figure 1a,b).³⁸ The resulting morphology of the graphene layers was examined by atomic force microscopy (AFM). These measurements yielded an apparent height difference of 0.89 nm between the regions of graphene supported by silicon and those suspended over holes (Figure 1c). The fwhm of the AFM peak provides an indication of the surface roughness of the graphene samples. Based on these measurements, the roughness of suspended and supported graphene layers was found to be 1.72 and 5.31 nm, respectively, indicating that the transferred graphene was of reasonably good quality. The contrast in the surface stiffness of the suspended and supported regions of the graphene sample was used to map the overall structure (Figure 1d). The formation of graphenesilicon antidot arrays with a fixed lattice constant a and increasing hole radii r was identified by the surface stiffness mapping technique [Figure 1d (i-vi)]. The hexagonal symmetry was present for all samples, with limited disorder from polymer residues, as shown in Figure 1d (i-vi) and in the corresponding two-dimensional Fourier transforms in Figure 1d(i'-vi').

In order to isolate the contribution of the graphene layer to modification of the optical response of the patterned substrate, we selectively etched away half of the graphene layer using an oxygen plasma (see Supporting Information, Figure S5a). We determined the precise position of the graphene on the substrate by Raman spectroscopy (Figure S5b), making use of the fact that a free-standing graphene monolayer exhibits a stronger Raman signal than that of a supported graphene monolayer.³⁹

For broadband optical characterization of the structure in the infrared, we probed the response of the sample using a commercial Fourier transform infrared spectrometer (Vertex, Bruker Optics), collecting the IR spectra in a reflection geometry. To this end broadband light from a thermal source was directed onto the sample at normal incidence through an aperture of 100 μ m × 20 μ m size. We then measured the reflectance *R* from the graphene-covered structure and the reflectance *R*₀ from an uncovered reference region of the photonic crystal. We characterize the influence of the graphene by its extinction ratio *ER* inferred from the reflectivity measurements: *ER* = 1 - *R*/*R*₀.

The reflectance from the graphene-covered and uncovered reference structures (Figure S1) were simulated using the CST Microwave Studio package⁴⁰ with the time-domain solver under the assumption of periodic boundary conditions. The relevant optical properties of silicon and silica (see Supporting

Information, Figure S2a,b) were taken from the refs 41 and 42, respectively. The response of the graphene monolayer was modeled as a sheet of thickness of $\Delta = 1$ nm, with an effective dielectric permittivity of $\varepsilon_{\rm G}(\omega) = 1 + i\sigma_{\rm S}(\omega)/\varepsilon_0\omega\Delta$, where ω is the angular frequency and $\sigma_{\rm S}(\omega)$ is the sheet conductivity of graphene. For the latter, we made use of the expression from ref 43 (see Supporting Information for further details), which includes both the intra- and interband contributions to the conductivity and also accounts for the effects of finite temperature *T*:

$$\sigma_{\rm S}(\omega) = \frac{2e^2k_{\rm B}T}{\pi\hbar^2} \ln\left[2\,\cosh\!\left(\frac{E_{\rm F}}{2k_{\rm B}T}\right)\right] \times \frac{i}{\omega + i\gamma} + \frac{e^2}{4\hbar} \left[H\!\left(\frac{\omega}{2}\right) + \frac{4i\omega}{\pi} \int_{-\infty}^{0} \mathrm{d}x \frac{H(x) - H\!\left(\frac{\omega}{2}\right)}{\omega^2 - 4x^2}\right]$$

where $H(x) = \frac{\sinh(\hbar x/k_{\rm B}T)}{-\frac{1}{2}\left(E_{\rm F}\left(1-\frac{\omega}{2}\right) + \frac{1}{2}\left(E_{\rm F}\left(1-\frac{\omega}{2}\right)\right)\right)}$

$$\cosh(E_{\rm F}/k_{\rm B}T) + \cosh(\hbar x/k_{\rm B}T)$$
$$= \frac{1}{2} \left[\tanh\left(\frac{\hbar x + E_{\rm F}}{2k_{\rm B}T}\right) + \tanh\left(\frac{\hbar x - E_{\rm F}}{2k_{\rm B}T}\right) \right]$$

In this description, there are two parameters describing the state of the graphene: the Fermi energy (or, rigorously, the chemical potential) $E_{\rm F}$ and the carrier scattering rate γ . In our simulations, we chose $E_{\rm F} = 0.3$ eV, a value comparable to the range of 0.25–0.35 eV measured by terahertz spectroscopy for unintentionally doped and transferred graphene layers.^{44,45} For the scattering rate, we used $\gamma = 2.0 \times 10^{13} \text{ s}^{-1}$, close to experimentally measured value of $\gamma = 2.3 \times 10^{13} \text{ s}^{-1}$ for CVD graphene⁴⁶ (see Supporting Information, Figure S2c).

PLASMONIC REGIME

In the mid-IR spectral region, we expect light–matter interactions to be dominated by the plasmonic modes of graphene. For our structures, the lattice constant *a* is much smaller than the wavelength of the light in this spectral range, so the membrane can be considered to be an effective homogeneous dielectric layer for the optical (but not plasmonic) waves (Supporting Information, Figure S2d, for the effective refractive index). For a free-space wavelength of $\lambda_0 = 10 \ \mu m$ (1000 cm⁻¹), the effective wavelengths for the plasmons in graphene are 352 and 54 nm for the supported and suspended regions, respectively, with corresponding propagation lengths of 264 and 41 nm (see Supporting Information, Figure S3).

Strong plasmonic coupling can occur if the size of a resonator in the structure is nearly equal to an integral number of effective wavelengths of the guided wave. In the case of a hole radius of r= 100 nm, the size of the silicon region between the edges of nearest neighboring holes is 215 nm. Based on these simple considerations, we expect to be able to excite the second-order plasmonic mode (with an effective wavelength about 112 nm around 700 cm⁻¹) at the silicon–graphene–air interface. (Excitation of the first-order mode would lie below 500 cm⁻¹ and is consequently outside of our experimental spectral range.) Plasmons can also be excited at the air–graphene–air interface at higher frequencies, with the first-order resonance occurring at a frequency around 1200 cm⁻¹. Due to the short propagation



Figure 2. Extinction spectra for graphene on a photonic crystal in the plasmonic regime in mid-IR range. (a) Measured and (b) simulated extinction spectra of graphene covering a 250 nm thick photonic crystal membranes with fixed lattice constant of a = 415 nm and increasing hole radius (r = 80, 90, 100, 110, 120, and 140 nm). A cumulative vertical offset of 50% has been included in the spectra for clarity. The peak around 1100 cm⁻¹ comes from the silica material absorption. Inset: Top view of the in-plane electric field profile of the mode corresponding to the peak in a false-color map.



Figure 3. Graphene extinction spectra showing coupling with photonic resonance in the near-IR range. (a) Measured extinction spectra of graphene covering a 250 nm silicon film (gray dashed curve) and photonic crystal membranes with a fixed lattice constant a = 415 nm and increasing hole radii from 80 to 140 nm (light blue). The solid blue curves are based on a Fano resonance model. A vertical offset of 30% between successive curves has been added for clarity. (b) Numerically simulated extinction spectra for the corresponding photonic crystal membranes. Inset: The vertical electric field amplitude profile for the structure at the resonant frequency. The dashed line shows the position of the graphene layer.

length of the plasmon, the quality factor of the resonator is expected to be relatively low and the resonance broad.

These expectations are confirmed by our experiment and simulations, as shown in Figure 2a,b. The plasmonic peak in the range below 1000 cm⁻¹ exhibits a gradual blue shift with increasing hole radius, that is, with decreasing size of the supported graphene layer. This basic trend, shown by blue arrows in Figure 2, is consistent with excitation of silicongraphene-air plasmonic modes. The inset in Figure 2b shows the rapid in-plane spatial oscillations of the electric field distribution at the associated resonance, corresponding to the second-order plasmonic mode in the supported graphene layer. The peak near 1100 cm⁻¹ is associated with a well-known phonon resonance in silica. At this frequency the reflectances Rand R_0 are close to zero, which leads to errors in calculating the extinction ratio ER = $1 - R/R_0$. Near 1100 cm⁻¹, a local maximum is predicted in the simulations for a hole radius of 80 nm, while a local minimum is expected for the other hole radii (see Figure 2b). In the experiment spectra, however, only a local maximum is observed (Figure 2a). The strong absorption of silica suppresses the air-graphene-air plasmonic resonances

that would otherwise be expected in the range above 1200 $\mbox{cm}^{-1}.$

PHOTONIC REGIME

For a Fermi energy of $E_{\rm F} = 0.3$ eV, interband transitions turn on for frequencies above 4830 cm⁻¹. In the higher-frequency range of 5500–7700 cm⁻¹, where photonic crystal resonances are present, graphene then behaves as an absorptive material with a nearly constant real sheet conductivity of $\sigma_{\rm S}(\omega) = \sigma_0 =$ $e^2/4\hbar$. The measured extinction spectra ER = $1 - R/R_0$ in Figure 3a exhibit a resonance corresponding to the first Fabry– Perot photonic resonance (compare the frequency position of the resonance to the kink in effective index of the membrane in Figure S2d). The feature in the extinction spectra exhibits a systematic blue shift with increasing hole radius. The experimental spectra (Figure 3a) could be fit well by Fano line shapes.

Figure 3b shows the corresponding simulation of our structure. The structure consists of several relatively thick layers (the 250 nm thick silicon photonic crystal membrane, a 500 nm thick air gap, and the 1500 nm thick silica layer above



Figure 4. Calculated enhancement of absorption by plasmonic effects in mid-IR range. (a) Absorption of graphene (with $E_F = 0.7 \text{ eV}$) on a silicon photonic crystal membrane (a = 100 nm, w/a = 0.1, t = 100 nm) with (red dotted curve) and without (gray solid curve) a back mirror reflector (with an air gap of 1600 nm). The field profiles at certain frequencies are shown in the inset. A maximum absorption of 87% is achieved by increasing Fermi level in graphene to 0.7 eV and setting the air gap thickness to 1600 nm (see the inset of b). (b) Absorption peak for four plasmonic modes (1–4, see panel a) vs the thickness of the air gap.

the bulk silicon substrate, see Figure S1). The presence of these layers leads to multiple resonances in the spectral range of the measurements (see Supporting Information). However, a single resonance has a dominant contribution in the experimental frequency range of $5500-7700 \text{ cm}^{-1}$. The simulations (Figure 3b) are seen to reproduce the observed blue shifts with increasing hole radius. The electric field distribution is illustrated in the inset of Figure 3b, which shows that the field is concentrated around the graphene layer, thus maximizing its interaction with the photonic mode.

To explore designs for optimized absorbance, we consider graphene on a simplified one-dimensional photonic crystal (Figure 4) with period a, thickness t, and air hole width w. The dependence of the absorbance on these structural parameters is discussed in the Supporting Information S1.3. The electric fields at resonant frequencies represent the whole range of possible surface plasmonic modes (Figure 4a, gray curve), including silicon-graphene-air and air-graphene-air modes, mixed modes, and photonic modes (see the inset for the field maps).

In the case of coupling to the photonic modes, a reasonable approach is to optimize the geometrical parameters so that the photonic modes confined in the photonic crystal plane can achieve higher quality factors. For example, increasing the period *a* to 500 nm for a thick silicon membrane of t = 500 nm causes the absorbance to grow from a few percent to 18% (see Supporting Information, S1.3). The absorption can be maximized by satisfying the critical coupling criterion in which the photon loss rate from leakage equals the graphene absorption.^{29,30,47} Such solutions are, however, difficult in the plasmonic regime, since plasmonic modes experience greater damping rates.

An alternative approach to increasing the absorbance in both the plasmonic and photonic regimes is to use a back reflector (red curve in Figure 4a). The quality factor of all optical modes (shown in the insets of Figure 4a) can be improved using a back reflector, with a controlled air gap between the silicon membrane and metal reflector. For example, adding a metallic mirror with an air spacer of thickness $t_{air} = 1600$ nm below the t= 100 nm thick membrane with graphene ($E_{\rm F} = 0.7$ eV) induces an increase in absorption from 18 to 87%, as shown in Figure 4a. For higher doping levels, the absorption for each plasmonic mode is maximized for a specific air gap thickness (Figure 4b).

As we have shown in this paper, graphene combined with a photonic crystal membrane offers a rich playground for controlling light—matter interactions in a platform compatible with silicon-based CMOS fabrication technology. We have delineated several different regimes for the enhancement of the absorption of IR radiation of a graphene monolayer placed on a silicon membrane patterned with a two-dimensional photonic crystal lattice. The enhancement, as observed experimentally and predicted theoretically, is a direct consequence of light coupling to plasmonic and photonic modes.

We have classified various regimes of light interaction for the graphene-photonic crystal composite structure: the metamaterial, plasmonic, photonic, and diffraction grating regimes, according to the relation of their effective wavelengths to the structural parameters of the photonic crystal. These different regimes may be suitable for different applications. The metamaterial regime, mainly in the terahertz to mid-IR range, may be of value for tunable absorbers, filters, and modulators. The plasmonic regime in mid-IR can be used, in addition to the aforementioned applications, for sensing due to the extreme confinement of graphene plasmons close to the surface. The photonic regime is suitable for photodetection, since absorption of photons in graphene may generate a photocurrent.

ASSOCIATED CONTENT

S Supporting Information

The Supporting Information is available free of charge on the ACS Publications website at DOI: 10.1021/acsphotonics.5b00209.

Simulated materials and structures; graphene plasmon properties; absorbance of graphene-covered 1D silicon subwavelength gratings; Raman characterization of the graphene-on-photonic crystal structures; effective index calculations and the reflectivity of multilayer structures; Fano fits to the substrate guided modes in near-IR region (PDF).

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Notes

The authors declare no competing financial interest.

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Supporting information for Photonic and plasmonic guided modes in graphene-silicon photonic crystals

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S1. Theoretical

S1.1. Simulated materials and structures

The simulated structure (Figure S1) corresponds to the fabricated one. Refractive indices of silicon¹ and silica² are shown in Figure S2a-b, respectively. Graphene's conductivity in the random phase approximation can be calculated ³ as

$$\sigma_{S}(\omega) = \frac{2e^{2}k_{B}T}{\pi\hbar^{2}}\ln\left[2\cosh\left(\frac{E_{F}}{2k_{B}T}\right)\right]\frac{i}{\omega+i\gamma} + \frac{e^{2}}{4\hbar}\left[H\left(\frac{\omega}{2}\right) + \frac{4i\omega}{\pi}\int_{0}^{\infty}dx\frac{H(x)-H\left(\frac{\omega}{2}\right)}{\omega^{2}-4x^{2}}\right],$$
(S2)

where *e* is elementary charge; k_B is Boltzmann's constant; *T* is absolute temperature; \hbar Planck's constant; *y* damping rate and H(x) is defined as:

$$H(x) = \frac{\sinh\frac{\hbar x}{k_B T}}{\cosh\frac{E_F}{k_B T} + \cosh\frac{\hbar x}{k_B T}} = \frac{1}{2} \left[\tanh\left(\frac{\hbar x + E_F}{2k_B T}\right) + \tanh\left(\frac{\hbar x - E_F}{2k_B T}\right) \right]$$
(S3)

Graphene's conductivity for $E_F = 0.3 \text{ eV}$, $\gamma = 2 \times 10^{13} \text{ s}^{-1}$ and T = 300 K is shown in Figure 2c. If the interband contribution to the conductivity is negligible, that is the case for $\hbar \omega < 2E_F$ and the electrochemical potential is larger than thermal fluctuation energy $E_F > k_B T$, graphene's conductivity can be described with Drude formula

$$\sigma_S(\omega) = \frac{e^2 E_F}{\pi \hbar^2} \frac{i}{\omega + i\gamma}$$
(S4)



Figure S1. Simulated structure consists of a silicon photonic crystal membrane (thickness d = 250 nm, lattice constant a = 415 nm) suspended above silica (1.5 µm) on silicon substrate.

We restored the effective index of the suspended photonic crystal membrane from reflection and transmission simulation⁴. The effective index decrease with hole radii increase due a decreasing silicon filling fraction. A kink in the spectra shifting from 6000 to 7000 cm⁻¹ corresponds to the first Fabry-Perot resonance condition $d = \lambda_0/2n_{eff}$.



Figure S2. Effective index of the photonic crystal membrane depending on holes radii. The refractive index of silicon and silicon are given in ref. 1 and ref. 2 respectively. surface conductivity of graphene in units of $\sigma_0 = e^2/4\hbar$ ($E_F = 0.3 \text{ eV}$, $\gamma = 2 \times 10^{13} \text{ s}^{-1}$, T = 300 K). Simulations were done in CST Microwave Studio⁵ with time-domain solver, rectangular mesh

and effectively periodic (x-axis perfect electric conductor, y-axis perfect magnetic conductor, zopen) boundary conditions. Fine spatial discretization was needed for consistent results (for example, 1 nm thick graphene layer was discretized with the step of 0.1 nm). Typical time for one simulation was 6 hours on 12 CPUs (3 GHz), 48 GB RAM computer.

S1.2 Graphene plasmons

Dispersion of transverse magnetic (TM) plasmons in graphene layer placed between two dielectrics with the permittivities ε_1 and ε_2 is described by the dispersion equation⁶

$$\frac{\varepsilon_1}{\sqrt{q^2(\omega)-\varepsilon_1}} + \frac{\varepsilon_2}{\sqrt{q^2(\omega)-\varepsilon_2}} + i\sigma_S(\omega)Z_0 = 0$$
(S1)

where $q = \beta/k_0$ is the normalized propagation constant or in other words effective mode index (β is the propagation constant and $k_0 = \omega/c$ is the wavenumber in vacuum), σ_S is the surface conductivity of graphene and $Z_0 = \sqrt{\mu_0/\varepsilon_0} = 1/c\varepsilon_0 = 120\pi[\Omega]$ is the free-space impedance.

Taking into account graphene's plasmons' large effective index $q \gg 1$ and typical dielectrics have permittivity in the range of 1-12, the dispersion relation can be simplified as:

$$q(\omega) = \frac{(\varepsilon_1 + \varepsilon_2)\pi\hbar^2}{Z_0 e^2 E_F} (\omega + i\gamma)$$
(S5)



Figure S3. Effective index (a), effective wavelength (b) and propagation length (c) of plasmons in graphene suspended in air (black line) or supported on silicon (red line). Graphene's electrochemical potential is $E_F = 0.3$ eV and damping rate $\gamma = 2 \times 10^{13}$ s⁻¹.

Propagation constant (see the effective mode index for $E_F = 0.3$ eV and $\gamma = 2 \times 10^{13}$ s⁻¹ in Figure S3a) depends on the graphene's surrounding and thus the plasmons propagating on suspended graphene and

graphene on silicon have different speed (effective index), thus forming plasmonic crystal or metamaterial (another way to form it is to structure graphene ⁷). Typical plasmon wavelength (Figure S3b) as well as propagation length (Figure S3c) range from a few tens to a few hundreds nanometers in the frequency range of interest (500-3000 cm⁻¹).

S1.3. Graphene covered 1D silicon subwavelength grating

For a better understanding of the photonic and plasmonic regimes we simulated graphene on a simplified one-dimensional photonic crystal (see Figure S4) with a period a, thickness t and air hole width w. The absorbance spectrum revealed a bunch of resonances. For a fixed period a = 100 nm and increasing air filling fraction w/a (Figure S4a) we observe reduction of number of silicon-graphene-air resonances and their blueshift that is consistent with the previously observed excitation of the plasmons on supported part (with decreasing silicon size the resonant regulated part for each of the plasmonic regimes of the plasmonic increase). Meanwhile the air-graphene-air plasmonic modes redshift (Figure S4a).

For the fixed w/a ratio and increasing grating period a (Figure S4b) there is observed a red-shift (resonator size becomes larger) with a trend resonance broadening. For the period a = 500 nm we can hardly distinguish more than one resonant peak whereas at a = 100 nm there are many. The reason for this is clear if we remember the typical propagation length for the supported graphene plasmons (see above) are less than 100 nm. For the resonator size of several hundreds of nm a plasmon excited at the edge of silicon decays before reaching the opposite side of the resonator, thus the resonance cannot be formed (in other words, the quality factor of the resonator is very low).



Figure S4. Simplified 1D photonic crystal consisting of silicon subwavelength grating and graphene ($E_F = 0.3 \text{ eV}$) in air. (a) Absorbance for a = 100 nm, t = 100 nm and varying w/a = 0.1- 0.9. Silicon-graphene-air plasmonic modes (insets 1-3) exhibits blue shift and reduction of number of modes with increasing w/a, whereas air-graphene-air mode redshifts (inset 4). (b) Absorbance for w/a = 0.1, t = 100 nm and varying period a = 100 - 500 nm. Silicon-graphene-air modes redshift and broaden with period a increase. (c) Absorbance for a thick membrane t= 500 nm, w/a = 0.1 and varying period a = 100 - 500 nm. Plasmonic modes exhibit a similar behavior to the case (b) in the low frequencies, whereas in the high frequencies photonic modes (insets 5 and 6) are observed.

In the previous cases (Figure S4a-b) the silicon membrane was assumed t = 100 nm thick. In low frequencies, in principle, there are no principal differences between thick and thin membranes (as soon as the membrane is still subwavelength). Small thickness does not allow for photonic modes excitation and guiding. If we increase the thickness to t = 500 nm plasmonic modes exhibit qualitatively the same behavior in the low frequencies, while in the high frequencies absorbance peaks corresponding to photonic modes appear (Figure S4c). The electric fields at resonant frequencies represent the whole "zoo" of possible excitations (Figure S4, insets 1-6), including silicon-graphene-air and air-graphene-air plasmonic and silicon grating photonic modes.

S2. Experimental



S2.1 Raman characterization of graphene-on-photonic crystal structure

Figure S5. (a) Optical microscope image of device layout, with strips of silicon superlattice with hole radius r decreasing from 140 to 80 nm in step of 10 nm (left to right). Graphene covers the shadowed area on top. The dashed square marks the region of FTIR window. (b) Raman spectrum for graphene superlattice with different radius versus lattice constant ratio r/a.

S2.2 Effective index calculation and reflectivity of multilayer structure

The suspended porous silicon thin film is 250nm thick (*d*) with silicon filling factor (δ) of 64%~88% as the hole radius increasing from 80nm to 140nm. The effective refractive index of the porous silicon thin film can be derived from the Maxwell-Garnett equation:

$$n_{eff} = \sqrt{\frac{2(1-\delta)n_{air}^{2} + (1+2\delta)n_{Si}^{2}}{(2+\delta)n_{air}^{2} + (1-\delta)n_{Si}^{2}}}$$
(S6)

where the refractive index of silicon n_{si} =3.42 in IR range. Transfer-matrix method is then applied to derive reflectance (r) for electromagnetic field normally incident onto the porous silicon thin film with effective wavenumber $k_{eff} = 2\pi n_{eff}/\omega$, suspended in air (with vacuum wavenumber k_0)⁸:

$$r = \frac{-k_{eff} \sin k_{eff} d + (k_0^2 / k_{eff}) \sin k_{eff} d}{k_{eff} \sin k_{eff} d + (k_0^2 / k_{eff}) \sin k_{eff} d + i2k_0 \cos(k_{eff} d)}$$
(S7)

The reflection spectrum ($R = |r^2|$) superimposed on the incident thermal source spectrum can be directly measured (Figure S6a), and compared to the simulated reflectance (inset of Figure S6a). The single atomic layer graphene exerts little modification on the absolute reflection spectrum (red solid curve in Figure S6a) compared to the substrate (grey dashed curve). The broadband reflection spectrum with controlled hole radius can be well described by the Transfer-matrix method (Figure S6b).



Figure S6. Measured reflection spectrum for graphene-silicon superlattice. (a) Absolute reflection spectrum of 250nm silicon thin film and photonic crystals with hole radius increasing

from 80-140 nm, in step of 10nm (from top to bottom), with (red solid curve) and without (grey dashed curve) coverage. Inset: reflected signal at 4000cm-1 wavenumber normalized by the thin film silicon. Red solid circles/grey empty squares: with/without graphene coverage. The dashed line is from simulation as shown in b. (b) Calculated reflection spectrum as shown in (a).

S2.3 Fano fit to the substrate guiding modes in near IR region

The extinction spectrum in the reflection, $1-R/R_0$, can be fitted by Fano resonance lineshape to experiments^{9,10} (Figure S7a):

$$1 - R / R_0 = A \frac{\left(q + \frac{\omega - \omega_0}{\Gamma / 2}\right)^2 + b}{1 + \left(\frac{\omega - \omega_0}{\Gamma / 2}\right)^2}$$
(1)

Where Γ_0 is the resonance frequency of the substrate guiding mode, and can be deterministically shifted by the substrate parameter; q is the asymmetry parameter, and fitted to be around -3. *b* is the screening parameter. A is amplitude of the resonance. *A* and *b* dependence on substrate parameter are fitted. The screening parameter b also limits the resonance width, Γ , which is the main effect of intrinsic losses in Fano resonances. The inverse of spectral width is the lifetime of the resonator, and fitted to be 0.1ps throughout the measurements in Figure S7b. At higher or lower loss rate, the Fano lineshape would have broader/narrow spectrum (Figure S7c), with fixed A=8%, b=-3. The screening parameter b (\approx 3) determines the contrast of the Fano lineshape (Figure S7d).



Figure S7. Graphene extinction spectrum coupling with photonic crystal guided resonance in near IR range. (a) Measured extinction spectra of graphene covered on 250nm thin film (grey dashed curve) and photonic crystals with fixed lattice constant and increasing hole radius (light blue dots). Solid blue curves are Fano resonance curve fitting. Vertical cumulative offest of 30% is added for clarity. Inset: Amplitude of Fano resonance versus r/a. (b) Guiding mode resonance frequency versus radius versus lattice constant ratio as extracted from the curve fitting in a. (c) Comparison of measured extinction spectrum (blue empty squares r=90nm) with the Fano spectrum with different lifetimes and (d) screening parameters.

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